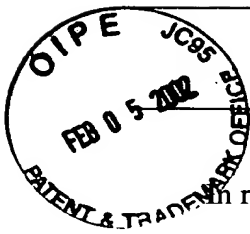


CA4/1762



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT

In re application of: Ricci *et al.*

Application No.: 09/408,921

Filed: September, 30, 1999

Title: PRETREATED GAS DISTRIBUTION PLATE

COPY OF PAPERS  
ORIGINALLY FILED

Attorney Docket No.:  
LAM1P118/P0539

Examiner: A. Powell

Group: 1763

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail to: Commissioner for Patents, Washington, DC 20231 on November 6, 2001.

Signed:

*Deborah Neill*

Deborah Neill

AMENDMENT B

Commissioner for Patents  
Box Non-Fee Amendment  
Washington, D.C. 20231

RECEIVED  
FEB 07 2002  
TC 1700

Sir:

This is in response to the Office Action mailed August 6, 2001.  
Reconsideration of the captioned application is respectfully requested.

IN THE CLAIMS:

Please AMEND claims 1, 5, 7, 8, 12-15 and 38-39 as follows:

1. (Twice-Amended) A gas distribution plate for use in a semiconductor fabrication apparatus including a semiconductor processing chamber; the gas distribution plate comprising:

a plurality of holes for passing process gases to the semiconductor processing chamber; and

a portion exposed to the process chemistry used in the semiconductor fabrication apparatus, wherein the portion of the gas distribution plate has substantially no micro-defects about 50 micrometers or greater, after machining, that may lead to contamination of a wafer located within said semiconductor processing chamber.